

SUBSTRATE PROCESSING METHOD AND SUBSTRATE PROCESSING APPARATUS

ABSTRACT

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Provided is a substrate processing method for processing a substrate by supplying a gas from a gas supply unit into a substrate processing space in a substrate processing apparatus. The gas supply unit comprises a plurality of gas sources, a flow path for circulating the gas from the plurality of the gas sources to
10 the substrate processing space, and a valve provided in the flow path to switch between opening and closing of the circulation of the gas. Pulse control is performed to cause the circulation of the gas to pulsate by alternately repeating the opening and closing of the circulation of the gas in the valve, wherein the duration of continuation of the pulse control and the number of times of opening the
15 circulation of the gas in the duration of continuation are controlled to control the flow volume of the gas.

Fig. 7